## **Supporting Information**

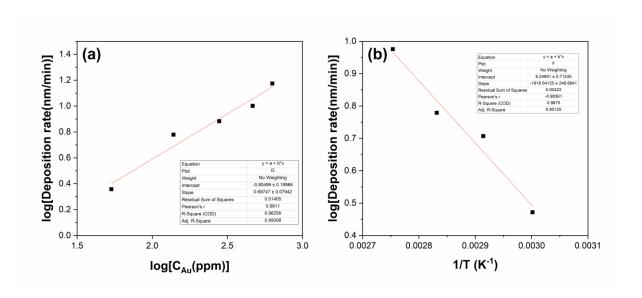
Thiourea-Based Extraction and Deposition of Gold for Electroless Nickel Immersion Gold Process

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**Figure S1.** Linear regression of (a) logarithm of deposition rate and gold concentration (b) logarithm of deposition rate and 1/T.



**Figure S2.** Photographic image of IG coating with the deposition condition of 50 ppm Au after a mild physical attack.